

SHEET 1 OF 6

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTORNEY DOCKET NO. 1945 P3/USA/SILICON		SERIAL NO.: N/A							
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Shen, et al.		FILING DATE: Herewith							
				GROUP: Unknown									
U.S. PATENT DOCUMENTS													
Examiner Initial		DOCKET NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>See</i>	A1	4	2	8	2	2	6	7	08/04/81	Küvel	427	38	
<i>See</i>	A2	4	4	3	3	2	2	8	02/21/84	Nishimatsu, et al.	219	10.55 R	
<i>See</i>	A3	4	4	6	5	5	3	2	08/14/84	Fukano	156	643	
<i>See</i>	A4	4	4	9	0	2	0	9	12/25/84	Hartman	156	643	
<i>See</i>	A5	4	5	0	2	9	1	4	03/05/85	Trumog et al.	156	643	
<i>See</i>	A6	4	5	7	6	6	9	2	03/18/86	Fukuta, et al.	204	165	
<i>See</i>	A7	4	7	0	5	5	9	5	11/10/87	Okudaira et al.	156	643	
<i>See</i>	A8	4	7	3	8	7	4	8	04/19/88	Kisa	156	643	
<i>See</i>	A9	4	7	8	6	5	5	2	11/22/88	Benzing	156	345	
<i>See</i>	A10	4	8	1	8	3	2	6	04/04/89	Liu, et al.	156	345	
<i>See</i>	A11	4	8	3	1	9	6	3	05/23/89	Saito, et al.	118	723	
<i>See</i>	A12	4	8	6	3	5	6	1	09/05/89	Freeman, et al.	156	646	
<i>See</i>	A13	4	8	6	7	8	4	1	09/19/89	Loewenstein, et al.	156	643	
<i>See</i>	A14	4	8	7	6	2	1	2	10/24/89	Koury	437	34	
<i>See</i>	A15	4	9	7	5	1	4	4	12/04/90	Yamazaki, et al.	156	643	
<i>See</i>	A16	4	9	9	2	1	3	6	02/12/91	Tachi et al.	156	643	
<i>See</i>	A17	4	9	9	4	4	1	0	02/19/91	Sun et al.	437	192	
<i>See</i>	A18	5	0	0	2	6	3	2	03/26/91	Loewenstein, et al.	156	643	
<i>See</i>	A19	5	0	1	3	3	9	8	05/07/91	Long et al.	156	643	
<i>See</i>	A20	5	0	3	5	7	6	8	07/30/91	Mu et al.	156	626	
<i>See</i>	A21	5	0	8	4	1	2	6	01/28/92	McKee	156	345	
<i>See</i>	A22	5	0	9	4	7	1	2	03/10/92	Becker et al.	156	643	
<i>See</i>	A23	5	1	1	0	4	0	8	05/05/92	Fujii et al.	156	643	
<i>See</i>	A24	5	1	1	0	4	1	1	05/05/92	Long	156	656	
<i>See</i>	A25	5	1	1	8	3	8	7	06/02/92	Kadomura	156	657	
<i>See</i>	A26	5	1	5	8	6	4	4	10/27/92	Cheung, et al.	156	643	
<i>See</i>	A27	5	1	6	0	4	0	7	11/03/92	Latchford et al.	156	656	
<i>See</i>	A28	5	1	6	4	3	3	0	11/17/92	Davis et al.	437	192	
<i>See</i>	A29	5	1	7	6	7	9	2	01/05/93	Fullowan et al.	156	652	
<i>See</i>	A30	5	1	8	8	9	8	0	02/23/93	Lai	437	193	

EXAMINER: *Shen, et al.*

DATE CONSIDERED: *2/6/02*

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

SHEET 2 OF 6

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTORNEY DOCKET NO. 1945.P3/USA/SILICON		SERIAL NO.: N/A							
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Shen, et al.		FILING DATE: Herewith							
				GROUP: Unknown									
U.S. PATENT DOCUMENTS													
Examiner Initial		DOCKET NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>AW</i>	A31	5	1	9	2	7	0	2	03/09/93	Tseng	437	47	
<i>AW</i>	A32	5	2	0	7	8	3	6	05/1993	Chang	134	1	
<i>AW</i>	A33	5	2	5	6	2	4	5	10/26/93	Keller, et al.	156	643	
<i>AW</i>	A34	5	2	8	1	3	0	2	01/25/94	Gabric, et al.	156	643	
<i>AW</i>	A35	5	2	8	2	8	9	9	02/01/94	Balmashonov, et al.	118	723 R	
<i>AW</i>	A36	5	3	1	2	5	1	9	05/17/94	Sakai, et al.	134	1	
<i>AW</i>	A37	5	3	1	8	6	6	8	06/07/94	Tamaki, et al.	156	662	
<i>AW</i>	A38	5	3	3	8	3	9	8	08/16/94	Szwejkowski, et al.	156	655	
<i>AW</i>	A39	5	3	5	4	4	1	7	10/11/94	Chung, et al.	156	643	
<i>AW</i>	A40	5	3	5	6	4	7	8	10/18/94	Chen, et al.	134	1	
<i>AW</i>	A41	5	3	5	8	6	0	1	10/25/94	Cathey	156	636	
<i>AW</i>	A42	5	3	7	8	3	1	1	01/03/95	Nagayama, et al.	156	643	
<i>AW</i>	A43	5	3	8	2	3	1	6	01/17/95	Hills, et al.	156	643	
<i>AW</i>	A44	5	3	8	9	1	9	7	02/14/95	Ishimaru	156	643	
<i>AW</i>	A45	5	4	1	3	9	5	4	05/09/95	Aydil, et al.	437	81	
<i>AW</i>	A46	5	4	3	1	7	7	2	07/11/95	Babie, et al.	156	643.1	
<i>AW</i>	A47	5	4	4	3	6	8	6	08/22/95	Jones, et al.	216	37	
<i>AW</i>	A48	5	4	4	9	4	1	1	09/12/95	Fukuda, et al.	118	723 MP	
<i>AW</i>	A49	5	5	1	4	6	2	2	05/07/96	Bornstein, et al.	437	189	
<i>AW</i>	A50	5	5	2	1	1	1	9	05/28/96	Chen, et al.	437	187	
<i>AW</i>	A51	5	5	2	9	1	9	7	06/25/96	Grewal	216	68	
<i>AW</i>	A52	5	6	2	0	6	1	5	04/15/97	Keller	138	720	
<i>AW</i>	A53	5	6	2	6	7	7	5	05/06/97	Roberts, et al.	216	67	
<i>AW</i>	A54	5	6	3	7	2	3	7	06/10/97	Oehrlein, et al.	216	67	
<i>AW</i>	A55	5	6	4	4	1	5	3	07/01/97	Keller	257	324	
<i>AW</i>	A56	5	7	5	3	5	3	3	05/19/98	Saito	437	192	
<i>AW</i>	A57	5	7	5	6	4	0	0	05/26/98	Ye, et al.	438	710	
<i>AW</i>	A58	5	7	6	7	0	2	1	06/16/98	Imai, et al.	438	719	
<i>AW</i>	A59	5	7	8	8	7	7	8	08/1998	Shang, et al.	134	1	
<i>AW</i>	A60	5	7	8	8	7	9	9	08/04/98	Steger, et al.	156	345	
EXAMINER: <i>AW</i>										DATE CONSIDERED: <i>2/6/02</i>			
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SHEET 3 OF 6

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTORNEY DOCKET NO. 1945.P3/USA/SILICON		SERIAL NO.: N/A							
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Shen, et al.		FILING DATE: Herewith							
				GROUP: Unknown									
U.S. PATENT DOCUMENTS													
Examiner Initial		DOCKET NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>AW</i>	A61	5	8	1	1	0	2	2	09/02/98	Savas, et al.	216	68	
<i>AW</i>	A62	5	8	1	7	5	3	4	10/06/98	Ye, et al.	438	10	
<i>AW</i>	A63	5	8	4	3	2	3	9	12/01/98	Shrotriya	134	1.1	
<i>AW</i>	A64	5	8	4	9	0	9	2	12/15/98	Xi, et al.	134	1.1	
<i>AW</i>	A65	5	8	6	6	4	8	3	02/02/99	Shiau, et al.	438	720	
<i>AW</i>	A66	5	8	6	9	4	0	1	02/09/99	Brunemeier, et al.	438	710	
<i>AW</i>	A67	5	8	7	4	3	6	3	02/23/99	Hoh, et al.	438	721	
<i>AW</i>	A68	5	8	7	9	5	7	5	03/09/99	Tepman, et al.	216	68	
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	A71												
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EXAMINER: <i>AW</i>										DATE CONSIDERED: <i>2/6/02</i>			
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FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTORNEY DOCKET NO. 1945 P3/USA/SILICON				SERIAL NO.: N/A							
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Shen, et al.				FILING DATE: Herewith							
				GROUP: Unknown											
FOREIGN PATENT DOCUMENTS															
		DOCKET NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION		
													YES	NO	
<i>See</i>	B1	0	2	7	2	1	1	3	06/22/88	EP Application					
<i>See</i>	B2	0	3	1	4	9	9	0	05/10/89	EP Application					
<i>See</i>	B3	0	4	6	3	3	7	3	01/02/92	EP Application					
<i>See</i>	B4	0	5	1	6	0	4	3	12/02/92	EP Application					
<i>See</i>	B5	0	3	5	5	5	4	6	08/18/93	EP Application					
<i>See</i>	B6	0	6	9	7	4	6	7	02/21/96	EP Application					
<i>See</i>	B7	0	7	4	6	0	1	5	12/04/96	EP Application					
<i>See</i>	B8	0	7	9	0	6	3	5	02/05/97	EP Application					
<i>See</i>	B9	4	1	3	2	5	5	9	04/08/93	German Application					
<i>See</i>	B10	6	1	7	7	0	9	2	06/24/94	Japan				✓	
<i>See</i>	B11	7	0	2	9	8	7	9	01/31/95	Japan				✓	
<i>See</i>	B12	9	6	1	5	5	4	5	05/23/96	PCT				✓	
<i>See</i>	B13	62	0	4	0	7	2	8	08/15/85	Japan Abstract				✓	
	B14														
	B15														
	B16														
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DATE CONSIDERED: *2/6/02*

SHEET 5 OF 6

FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTORNEY DOCKET NO. 1945 P3/USA/SILICON		SERIAL NO.: N/A	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Shen, et al.			
				FILING DATE: Herewith		GROUP: Unknown	
OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)							
<i>AW</i>	C1	Aydi, et al., "Multiple Steady States in a Radio Frequency Chlorine Glow Discharge," <i>J. Appl. Phys.</i> , Volume 69, No. 1, January 1, 1991, pages 109-114					
<i>AW</i>	C2	Hillenius, S.J., et al., "A Symmetric Submicron CMOS Technology," <i>IEEE</i> , pages 252-255, 1986					
<i>AW</i>	C3	PCT Notification of International Search Report dated October 28, 1999					
<i>AW</i>	C4	PCT Notification of International Search Report dated February 4, 1999					
	C5						
	C6						
	C7						
	C8						
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	C17						
	C18						
	C19						
	C20						
EXAMINER		<i>Alan W. Chan</i>				DATE CONSIDERED <i>2/6/02</i>	
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							

5:10/10/2004 10:00:00 PTO-1449-001

February 18, 2000

PENDING U.S. PATENT APPLICATIONS

SHEET 6 OF 6

ATTORNEY DOCKET NO.: 1945.P3/USA/SILICON
 SERIAL NUMBER: N/A
 FILING DATE: HERewith
 INVENTORS: SHEN, ET AL.

EXAMINER INITIAL		PENDING U.S. PATENT APPLICATIONS
	D1	U.S. Patent Application entitled: "Method for Improved Cleaning of Substrate Processing System"; filed July 11, 1997; Serial No. 08/893,922; Inventors: Kao, et al. = 6,125,857
	D2	U.S. Patent Application entitled: "Apparatus for Improved Remote Microwave Plasma source for Use with Substrate Processing Systems"; filed April 23, 1997; Serial No. 08/839,111; Inventors: Kao, et al. = 6,028,762
	D3	U.S. Patent Application entitled: "Method and Apparatus for Determining the Endpoint in a Plasma Cleaning Process"; filed July 2, 1997; Serial No. 08/887,165; Inventors: Subrahmanyam, et al. = 6,071,426
	D4	U.S. Patent Application entitled: "Apparatus and Method for Efficient and Compact Remote Microwave Plasma Generation"; filed April 22, 1997; Serial No. 08/839,007; Inventor: Bhamagar = 6,029,602
	D5	U.S. Patent Application entitled: "Method and Apparatus for Pre-stabilized Plasma Generation for Microwave Clean Applications"; filed November 13, 1996; Serial No. 08/16,658; Inventors: Fong, et al. = 5,939,831
	D6	U.S. Patent Application entitled: "Inductively Coupled HDP-CVD Reactor"; filed May 29, 1997; Serial No. 08/865,018; Inventors: Redeker, et al. = 6,182,602
	D7	U.S. Patent Application entitled: "Symmetric Tunable Inductively Coupled HDP-CVD Reactor"; filed July 15, 1996; Serial No. 08/679,927; Inventors: Redeker, et al. = 6,170,428
	D8	U.S. Patent Application entitled: "Apparatus and Methods for Upgraded Substrate Processing System with Microwave Plasma Source"; filed March 5, 1997; Serial No. 08/811,627; Inventors: Tanaka, et al. = 6,039,821
	D9	U.S. Patent Application entitled: "Microwave Apparatus for In-situ Vacuum Line Cleaning for Substrate Processing Equipment"; filed October 30, 1996; Serial No. 08/741,241; Inventors: Pang, et al. = 6,045,618
	D10	
	D11	
	D12	
	D13	
	D14	

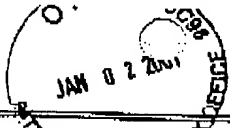
SHEET 1 OF 1

PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF ARTS CITED BY APPLICANT (Use several sheets if necessary)		ATTORNEY DOCKET NO. 1945.P3/SILICON/CLEANGAS SERIAL NO.: 09/507,629				
APPLICANT: SHEN, ET AL. FILING DATE: 3/18/00		GROUP: 1796				
U.S. PATENT DOCUMENTS						
Examiner Initial	DOCKET NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
See	AA 4 4 7 7 3 3 8 8 7 7 4 4 8 8	04/19/88	KISA	156	643	
See	AB 4 4 7 7 7 7 9 9 9 9 1 1	1/1989	DOCKREY	438	719	
	AC					
	AD					
	AE					
	AF					
	AG					
	AH					
	AI					
	AJ					
	AK					
FOREIGN PATENT DOCUMENTS						
	DOCKET NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION
						YES NO
	AL					
	AM					
	AN					
	AO					
	AP					
OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)						
	AQ					
	AR					
	AS					
	AT					
	AU					
	AV					
	AW					
	AX					
EXAMINER <i>Allen - Chen</i>				DATE CONSIDERED 2/6/02		
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FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTORNEY DOCKET NO. 001945 USA P03/ ETCH/ SILICON/3		SERIAL NO 09/507.629									
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT: Shen, et al.		FILING DATE: 02/18/2000									
						GROUP: 1746									
U.S. PATENT DOCUMENTS															
Examiner Initial		DOCKET NUMBER							DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE		
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<i>AW</i>	AB	5	6	5	1	8	5	6	07/29/97	Keller, et al	156	643.1			
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	AD														
	AE														
	AF														
	AG														
	AH														
	AI														
FOREIGN PATENT DOCUMENTS															
		DOCKET NUMBER							DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION		
													YES	NO	
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<i>AW</i>	AK	0	2	0	0	9	5	1	04/11/06	EP					
	AL														
	AM														
	AN														
OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)															
<i>AW</i>	AO	PCT Report dated 06/22/01, European Patent Office, P.B. 5818 Patentlaan 2 NL-2280 HV Rijswijk													
<i>AW</i>	AP	Zaleski, et al "Tungsten Silicide/Polysilicon Stack Etching using Mixed Fluorine Chlorine Chemistry in a High Density Plasma Chamber", Electrochemical Society Proceedings Volume 98-4, pages 203-209.													
<i>AW</i>	AQ														
EXAMINER <i>AW</i>															
DATE CONSIDERED 2/6/02															
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FORM PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT & TRADEMARK OFFICE			ATTORNEY DOCKET NO. 1945 P3/USA/SILICON		SERIAL NO 091507,629									
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT: Shell et al.		GROUP: <u>1796</u> UNKNOWN									
					FILING DATE: 02/18/2000											
U.S. PATENT DOCUMENTS																
Examiner Initial		DOCKET NUMBER								DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)		
<i>Lee</i>	AA	5	5	7	0	0	7	4	1	12/23/97	Liao	438	713 723			
<i>Lee</i>	AB	6	0	0	9	0	7	1	8	07/18/00	Hajime, et al.	438	714			
	AC															
	AD															
	AE															
	AF															
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FOREIGN PATENT DOCUMENTS																
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<i>Lee</i>	AJ	0	1	0	5	0	4	27	02/27/89	Japan					(x) Abstract only	
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<i>Lee</i>	AL	0	7	0	9	8	7	7	05/01/96	EP					x	
	AM															
	AN															
OTHER ART (Including Author, Title, Date, Pertinent Pages, etc.)																
<i>Lee</i>	AO	PCT Search Report dated 11/8/00.														
	AP															
	AQ															
EXAMINER <i>Allen O...</i>												DATE CONSIDERED <u>2/6/02</u>				
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 GROUP 700

FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	DOCKET NO. 001945 USA POMETCH/SILICON/JB	APPLICATION NO. 09/507,629
INFORMATION DISCLOSURE STATEMENT IN AN APPLICATION (Use several sheets if necessary)	APPLICANT: Shen, et al.	
	FILING DATE: 7/18/2000	GROUP ART UNIT: Unknown

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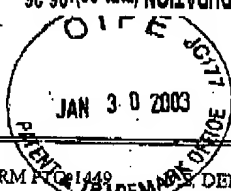
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SHEET 1 OF 1

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SHEET 1

FORM PTO-1449 DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE INFORMATION DISCLOSURE STATEMENT IN AN APPLICATION (Use several sheets if necessary)		DOCKET: 001945 USA P03/ETCH/SILICON/IB				APPLICATION NO: 09/307,629								
		APPLICANT: SHEN et al.												
		FILING DATE: 02/18/2000				GROUP ART UNIT: 1746 / 1763								
		U.S. PATENT DOCUMENTS												
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE								
AW	5,259,323	11/29/1993	HORI et al.			DUPLICATE								
AW	5,384,009	1/24/1995	MAK et al.											
AW	5,180,464	1/19/1993	TATSUMI et al.											
AW	6,270,634	8/7/2001	KUMAR et al.											
AW	6,125,859	10/3/2000	KAO et al.											
AW	5,861,233	1/19/1999	SEKINE et al.											
FOREIGN PATENT DOCUMENTS														
								DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	ABSTRACT	
													YES	NO
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)														
AW	Kimizuka, Masakatsu et al. "Pattern Profile Control in Magnetron reactive ion etching of Poly-Si." J. Vac. Sci. Technol. B 10(5), Sept/Oct 1992. pp. 2192-2196.													
EXAMINER: <i>Altan Olan</i> DATE CONSIDERED: 5/24/03														
EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.														

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